

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method of forming a plurality of films on a base, the method comprising:

forming a first film of the plurality of films in a first area of the base, the forming of the first film including an ejection of a first material from a first nozzle that is carried out during a first period; and

forming a second film of the plurality of films that is formed in a second area of the base and that is separated from the first film, the forming of the second film including an ejection of the first material from the first nozzle that is carried out during a second period,

the first film being formed when the ejection of the first material from the first nozzle during the first period is completed,

the base being provided in a first chamber during the first period,

the second film being formed when the ejection of the first material from the first nozzle during the second period is completed, and

the base being provided in the first chamber during the second period.

~~setting a plurality of relative positions of at least one nozzle to the base, the setting of the plurality of relative positions including moving at least one of the at least one nozzle and the base;~~

~~gasifying a first material by heating the first material to form the first material in a form of gas;~~

~~ejecting a first material in the form of gas from the at least one nozzle toward the base at each of the plurality of relative positions; and~~

~~detecting an ejection failure of the at least one nozzle.~~

2. (Currently Amended) The method according to Claim 1,
the base being provided in ~~a vacuum~~ an atmosphere that is adjusted to a pressure of 10^{-3} torr or less during at least a ~~period in which the ejecting of the first material in the form of gas is carried out~~ part of the first period.
3. (Currently Amended) The method according to Claim 1,
the base being provided in ~~a vacuum~~ an atmosphere that is adjusted to a pressure of 10^{-5} torr or less during at least a ~~period in which the ejecting of the first material in the form of gas is carried out~~ part of the first period.
4. (Currently Amended) The method according to Claim 1, the further comprising:
_____ detecting of the ~~an~~ ejection failure of the first nozzle. ~~at least one nozzle including a preliminary ejection of the first material in the form of gas to a preliminary ejecting area provided in a preliminary member provided in a predetermined area on the base,~~
and
_____ the plurality of films being to be formed in the predetermined area.
5. (Currently Amended) The method according to ~~Claim 1,~~ Claim 4,
_____ the detecting of the ejection failure of the ~~at least one~~ first ~~nozzle including a preliminary~~ an ~~ejection of the first material from the first nozzle to a third in the form of gas to a preliminary ejecting area provided in a preliminary member in a predetermined area on the base, and~~ base.
_____ the ejection failure being detected on the basis of an inspection of a preliminary film that is formed on the preliminary ejecting area by the preliminary ejection.
6. (Currently Amended) The method according to ~~Claim 5,~~ Claim 52,
_____ the inspection of the preliminary film being performed by a measurement of light-reflectivity of the preliminary film.

7. (Currently Amended) The method according to ~~Claim 5,~~ Claim 52,
_____ the inspection of the preliminary film being performed by a measurement of
light-transmissivity of the preliminary film.

8. (Currently Amended) The method according to Claim 1, further
~~comprising:~~ comprising
_____ forming a third film of the plurality of films that is formed on the first film, the
forming of the third film including an ejection of ~~ejecting~~ a second material in a form of gas
~~from the at least one nozzle, that is carried out during a third period.~~
_____ ~~the detecting of the ejection failure of the at least one nozzle being carried out~~
~~prior to the ejecting of the second material in the form of gas from the at least one nozzle.~~

9. (Currently Amended) The method according to Claim 1,
_____ the first material being ejected in a form gas from the first nozzle to the first
chamber during the first period. ~~A method of forming of plurality of films on a base, the~~
~~method comprising:~~
_____ ~~setting a first relative position of at least one nozzle to the base, the setting of~~
~~the first relative position including moving at least one of the at least one nozzle and the base;~~
_____ ~~forming a first film of the plurality of films on a first area of the base by~~
~~ejecting a first material in a form of gas from the at least one nozzle at the first relative~~
~~position;~~
_____ ~~setting a second relative position of the at least one nozzle to the base, the~~
~~setting of the second relative position including moving at least one of the at least one nozzle~~
~~and the base; and~~
_____ ~~forming a second film of the plurality of films on a second area of the base by~~
~~ejecting the first material in the form of gas from the at least one nozzle at the second relative~~
~~position.~~

10. (Currently Amended) The method according to Claim 9,

the first material being ejected in the form gas from the first nozzle to the first chamber during the second period. ~~base being provided in a vacuum atmosphere during at least a period in which the ejecting of the first material in the form of gas to the first area is carried out.~~

11. (Currently Amended) The method according to ~~Claim 9,~~Claim 53,

the second material being ejected in a form gas from the second nozzle to the first chamber during a third period in which the ejection of the second material from the second nozzle is carried out.

~~the base being provided in a vacuum atmosphere that is adjusted to 10^{-3} torr or less during at least a period in which the ejecting of the first material in the form of gas to the first area is carried out.~~

12. (Canceled)

13. (Currently Amended) The method according to ~~Claim 9,~~Claim 8, further comprising:

forming a ~~third~~ fourth film of the plurality of films ~~on the first film;~~ and
~~that is formed on the second film, the forming a of the fourth film of the plurality of films on including an ejection of the second film.~~ material that is carried out during a fourth period.

14. (Currently Amended) ~~The method according to Claim 9, further~~ A method of forming a plurality of films on a base, the method comprising:

forming a first film of the plurality of films in a first area of the base, the forming of the first film including an ejection of a first material from a first nozzle that is carried out during a first period; and

forming a second film of the plurality of films in a second area of the base, the second film being separated from the first film, the forming of the second film including an ejection of the first material from the first nozzle that is carried out during a second period,
the first film being formed when the ejection of the first material during the first period is carried out,

the base being provided in a first chamber during the first period,
the second film being formed when the ejection of the first material during the second period is completed, and

the base being provided in the first chamber during the second period.
~~detecting a positional deviation between a first position where a preliminary film is to be formed by ejecting the first material in the form of gas and a second position where the preliminary film is actually formed by ejecting the first material in the form of gas.~~

15. (Currently Amended) A method of manufacturing an electronic device, the method comprising:

forming at least one element of elements constituting a part of the electronic device being formed by using the method according to Claim 9.Claim 1.

16. (Currently Amended) The method according to Claim 15,
the first material ~~in the form of gas~~ being used for at least one of a conductive ~~layer, film,~~ a semiconductor ~~layer, film,~~ and an insulating ~~layer, film.~~

17. (Currently Amended) The method according to Claim 15, further ~~comprising~~ comprising:

providing a pattern prior to the ejecting of the first material from the first nozzle during the first period is carried out,~~in the form of gas,~~

the plurality of films being formed according to the pattern.

18. (Currently Amended) A method of manufacturing an electro-optical device,
the method comprising:

_____ including a plurality forming at least a part of the electro-optical elements,
device by the plurality of electro-optical elements being formed using the method according
to Claim 1.

19. (Currently Amended) ~~The method according to Claim 18;~~ A method of
manufacturing an electro-optical device, the method comprising using the method of claim 1
to form:

_____ at least a part of the electro-optical device; and
at least one of an electron-transporting layer, a hole-transporting layer, a light
emitting layer, and an electrode included in an the plurality of electro-optical elements
element included in the electro-optical device being a plurality of organic electroluminescent
elements each of which includes an electron-transporting layer, a hole-transporting layer, a
light-emitting layer, and electrodes, and
_____ the first material being used for at least one of the electron-transporting layer,
the hole-transporting layer, the light-emitting layer, and the electrodes.

20. (Previously Presented) The method according to Claim 19, further
comprising:

forming partitions that surround at least one of the light-emitting layer, the
electron-transporting layer and the hole-transporting layer.

21-30. (Canceled)

31. (Currently Amended) ~~The method according to Claim 1;~~ Claim 4,
the detecting of the ejection failure ~~of the at least one nozzle being carried out~~
using a sensor.

32. (Currently Amended) The method according to ~~Claim 9,~~ Claim 1, further comprising:

sensing at least one film of the plurality of films.

33. (Previously Presented) The method according to Claim 32,
the sensing of the at least one film including an irradiation of the at least one film with a light source.

34. (Previously Presented) The method according to Claim 32,
the sensor measuring at least one of a transmission light that transmits the at least one film and a reflection light that is reflected by the at least one film.

35. (Currently Amended) The method according to ~~Claim 32,~~ Claim 1,
~~the base being provided in a vacuum atmosphere that is adjusted to 10^{-3} torr or less during at least a period in which the ejecting the ejection of the first material in the form of gas is carried out from the first nozzle during the first period is carried out at a first position of the first nozzle relative to the base, and~~
the ejection of the first material from the first nozzle during the second period is carried out at a second position of the first nozzle relative to the base.

36. (Currently Amended) ~~A method of forming a plurality of films on a base, the ejecting~~ The method according to Claim 35,
further comprising:
moving a position of the first nozzle relative to the base from the first position to the second position.
~~ejecting a first material in a form of gas from a nozzle of a plurality of nozzles and a second material in a form of gas from a nozzle of the plurality of nozzles; and~~

~~_____sensing at least one film of the plurality of films by a sensor, the plurality of nozzles moving during at least a part of a period in which the ejecting is carried out, and each of the plurality of films including the first material and the second material.~~

37. (Currently Amended) The method according to Claim 1,
_____the first nozzle being one nozzle of a plurality of nozzles provided in a discharge head.~~A method of manufacturing an electronic device, at least one element of elements constituting the electronic device being formed using the method according to Claim 32.~~

38. (Currently Amended) ~~A method of manufacturing an electronic device, at least one element of elements constituting the electronic device being formed using the method according to Claim 36.~~The method according to Claim 1, further comprising:
_____sensing the first film by a sensor.

39. (Currently Amended) ~~A method of manufacturing an electro-optical device including a plurality of electro-optical elements, the plurality of electro-optical elements being formed using the method according to Claim 36.~~The method according to Claim 1, further comprising:
_____detecting a positional deviation between a first location on the base where the first film is actually formed and a second location on the base where the first film is to be formed.

40. (Currently Amended) The method according to Claim 18,
_____the plurality of electro-optical device including an elements being a plurality of organic electroluminescent elements each of which includes an electron transporting layer, a hole transporting layer, a light emitting layer, and electrodes, element, and

~~the first material and the second material film being used for at least one of the one of an electron-transporting layer, the a hole-transporting layer, the a light-emitting layer, layer and an electrode included in the organic electroluminescent element. the electrodes, and~~
~~————— a formation of the light emitting layer including a co-deposition of a host material and a guest material both of which are included in the light emitting layer.~~

41. (Currently Amended) ~~A method of manufacturing an electro-optical device including a plurality of electro-optical elements, the method comprising:~~The method according to Claim 1,

~~ejecting a first material in a form of gas from a the first nozzle being one of a plurality of nozzles and a second material in a form of gas from a second nozzle of the plurality of nozzles,~~

~~the plurality of nozzles being moved during at least a part of a period in which the ejecting of the first a third material in the form of gas and the second material in the form of gas is carried out, being ejected from a third nozzle of the plurality of nozzles during at least part of the first period, and~~

~~each of the plurality of electro-optical elements including a first layer that includes at least one of the first film including the first material and the second third material.~~

42. (Currently Amended) ~~A method of forming a plurality of films on a base, the method~~The method according to Claim 1, further comprising:

~~————— ejecting a first material in a form of gas from at least one nozzle toward the base at each of a plurality of relative positions; and~~

~~————— sensing by a sensor at least one film of the plurality of films each of which includes the first material,~~

performing a scanning movement of a head including the first nozzle. the at
~~least one nozzle being carried out during at least a part of a period in which the ejecting is~~
~~carried out.~~

43. (Currently Amended) ~~A method of forming a plurality of films on a base, the~~
~~method comprising:~~

~~_____ejecting a first material in a form of gas from a nozzle of a plurality of nozzles~~
~~and a second material in a form of gas from a nozzle of the plurality of nozzles; and~~

~~_____sensing at least one film of the plurality of films by a sensor,~~

~~_____a scanning movement of the plurality of nozzles being carried out during at~~
~~least a part of a period in which the ejecting is carried out.~~The method according to Claim 42,

_____the scanning movement of the head being performed during at least a part of a
fifth period between the forming of the first film and the forming of the second film.

44. (Currently Amended) The method according to ~~Claim 36,~~Claim 42,
_____the first nozzle being one nozzle of a

~~_____the plurality of nozzles being provided in a discharge the head.~~

45. (Previously Presented) The method according to Claim 44,
the discharge head being constructed to adjust a posture of the discharge head
by a θ direction adjusting mechanism, a Z direction adjusting mechanism, and a Y adjusting
mechanism.

46. (Previously Presented) The method according to Claim 45,
each of the θ direction adjusting mechanism, the Z direction adjusting
mechanism, and the Y adjusting mechanism being operated.

47. (Canceled)

48. (Currently Amended) ~~A method of forming a plurality of films on a base, the~~
~~method~~The method according to Claim 1, further comprising:

~~detecting an ejection failure of a first nozzle;~~
setting a first relative position of the first nozzle to the base, ~~the setting of the~~
~~first relative position including moving at least one of the first nozzle and the base;~~base
before the forming of the first film is carried out; and

~~ejecting a first material in a form of gas that is formed by gasifying the first~~
~~material by heating the first material from the first nozzle toward the base;~~

~~detecting an ejection failure of a second nozzle;~~
setting a second relative position of the ~~second~~ first nozzle relative to the base
before the forming of the second film is carried out. ~~base, the setting of the second relative~~
~~position including moving at least one of the second nozzle and the base; and~~

~~ejecting a second material in the form of gas that is formed by gasifying the~~
~~second material by heating the second material from the first nozzle toward the base.~~

49. (Currently Amended) The method according to ~~Claim 41,~~Claim 1, further
comprising:

~~setting a first relative position of the first nozzle relative to the base before the~~
ejection of

~~the ejecting of the first material from the first nozzle in the form of gas being~~
~~carried out during at least a part of a the first period in which the ejecting of the second~~
~~material in the form of gas is carried out; and~~

~~setting a second relative position of the first nozzle, relative to the base before~~
the ejection of the first material from the first nozzle during the second period is carried out.

50. (Currently Amended) ~~The method~~ A method of manufacturing an electro-
optical device, the method comprising:

~~forming at least a part of the electro-optical device by the method according to~~
Claim 41,

~~the first layer including each of the first material film and the second material film being at least a part of the electro-optical device.~~

51. (Currently Amended) ~~The method according to Claim 50,~~ A method of manufacturing an electro-optical device, the method comprising:

~~the plurality of forming at least part of the electro-optical device by the method according to Claim 55, elements being a plurality of organic electroluminescent elements,~~

~~each of the first material film and the second material film being at least a part of the electro-optical device, included in one of a light emitting layer, an electron transporting layer and a hole transporting layer that is included in each of the plurality of organic electroluminescent elements.~~

52. (New) The method according to Claim 5,
a preliminary film being formed by the ejection of the first material from the first nozzle to the third area provided on the base, and

the ejection failure being detected based on an inspection of the preliminary film.

53. (New) The method according to Claim 1, further comprising:
forming a third film of the plurality of films that is formed in a third area provided on the base different from the first area and that is separated from the first film, the forming of the third film including an ejection of a second material from a second nozzle different from the first nozzle.

54. (New) The method according to Claim 1, further comprising:
forming a third film of the plurality of films that is formed on a third area of the base different from the first area, the forming of the third film including an ejection of a second material from a second nozzle different from the first nozzle that is carried out during the first period.

55. (New) The method according to Claim 1,

a third material being ejected from the first nozzle during at least a part of the first period, and

the first film including the first material and the third material.

56. (New) The method according to Claim 50,
an organic electroluminescent element being include in the electro-optical device, and

the first film being one of an electron-transporting layer, a hole-transporting layer, a light-emitting layer and an electrode include in the organic electroluminescent element.

57. (New) The method according to Claim 51,
an organic electroluminescent element being include in the electro-optical device, and

the first film being one of an electron-transporting layer, a hole-transporting layer, a light-emitting layer and a an electrode include in the organic electroluminescent element.